

PATENT 0020-4652P

IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant:

Narihiro MOROSAWA et al. Conf.: 7107

Appl. No.:

09/471,173

Group:

2826

Filed:

December 23, 1999

Examiner: K. Ouinto

For:

INSULATED GATE TRANSISTOR AND PROCESS

FOR FABRICATING THE SAME (To be

Amended)

REPLY UNDER 37 C.F.R. § 1.111

Assistant Commissioner for Patents Washington, DC 20231

March 3, 2003 (Monday)

Sir:

In reply to the Examiner's Office Action dated October 2, 2002, the period for response having been extended two months to March 2, 2003, the following amendments and remarks are respectfully submitted in connection with the above-identified application.

IN THE TITLE:

Please amend the title to read: "INSULATED GATE TRANSISTOR HAVING A GATE INSULATOR CONTAINING NITROGEN ATOMS AND FLUORINE ATOMS".

IN THE CLAIMS:

Please amend the following claim:

03/04/2003 JBALINAN 00000147 09471173

01 FC:1252

410.00 OP

